

- A<sub>1</sub>
3. (Amended) A process according to claim 1 wherein the underlayer comprises a silicon oxide.
4. (Amended) A process according to claim 1 wherein the underlayer comprises a silicon oxide containing carbon.
5. (Amended) A process according to claim 1 wherein the pyrolytic deposition of the underlayer comprises contacting the glass substrate with a fluid mixture containing a silicon source, an oxygen source and a carbon source under conditions such that a silicon oxide layer, preferably containing carbon, is deposited.
6. (Amended) A process according to claim 5 wherein the fluid mixture is a vapor mixture.
7. (Amended) A process according to claim 1 wherein the underlayer comprises silicon oxide containing nitrogen.
8. (Amended) A process according to claim 1 wherein the underlayer is deposited on the glass substrate when the glass substrate is at a temperature in the range 450°C to 800°C.
- Sub B<sub>1</sub>
- TELETYPE

B<sub>2</sub> 5-17  
10. (Amended) A process according to claim 1 wherein the underlayer is deposited on to a glass ribbon during the float glass production process at substantially atmospheric pressure.

B<sub>3</sub>  
12. (Amended) A process according to claim 1 wherein the reflective metal layer comprises silver or aluminium.

13. (Amended) A process according to claim 1 wherein an anti-reflection layer is deposited by a vacuum deposition process on to the coated glass after deposition of the reflective metal layer.

B<sub>4</sub>  
16. (Amended) A process according to claim 13 wherein a second reflective metal layer and a second anti-reflection layer are sequentially deposited by a vacuum deposition process after deposition of the first anti-reflection layer.

17. (Amended) A process according to claim 1 additionally comprising a heat treatment step wherein the heat-treatable low emissivity coated glass is subjected to a temperature in the range 400 to 750°C in an oxidising atmosphere.

B<sub>5</sub>  
19. (Amended) A process according to claim 17 wherein the visible transmission of the coated glass is increased by the heat-treatment step.

sub B<sub>7</sub>  
20. (Amended) A coated glass produced by a process according to claim 1.

C<sub>6</sub>  
24. (Amended) A coated glass according to claim 21 wherein the underlayer has a refractive index in the range 1.5 to 3.

25. (Amended) A coated glass according to claim 21 wherein the underlayer has a thickness in the range 30 to 100 nm.

26. (Amended) A coated glass according to claim 21 wherein the reflective metal layer has a thickness in the range 5 to 30 nm.

C<sub>7</sub>  
28. (Amended) A coated glass according to claim 21 wherein the anti-reflection layer has a thickness in the range 30 nm to 90 nm.

29. (Amended) A coated glass according to claim 21 wherein the coated glass has a normal emissivity of below 0.2.